

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Maruyama et al.
Appl. No. : 10/522,036
Filed : January 19, 2005
For : CHEMICAL AMPLIFICATION
TYPE POSITIVE PHOTORESIST
COMPOSITION AND RESIST
PATTERN FORMING METHOD
Examiner : Lee, Sin J
Group Art Unit : 1752

AMENDMENT AND RESPONSE TO OFFICE ACTION

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

In response to the final Office Action mailed **September 20, 2007**, please consider the following amendments and remarks.

Amendments to the claims begin on page 2 of this paper.

Remarks begin on page 10 of this paper.

Please
Enter
S.J.L.
11-23
2007